

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	2	("5837420").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/25 14:22
S2	3	("5347040"   "5569784"   "5580695").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2004/09/25 14:34
S3	17	("5837420").URPN.	USPAT	OR	ON	2004/09/25 17:08
S4	19034	\$BENZENESULFONATE	USPAT	OR	ON	2005/04/20 11:31
S5	1966	(PHOTOACID ACID) ADJ GENERATOR	USPAT	OR	ON	2005/04/20 11:31
S6	251	S4 AND S5	USPAT	OR	ON	2004/09/25 17:40
S7	602594	POSITIVE	USPAT	OR	ON	2004/09/25 17:41
S8	3301	(PHOTOACID ACID) ADJ LABILE	USPAT	OR	ON	2005/04/20 11:31
S9	621337	RESIN RESIST PHOTORESIST	USPAT	OR	ON	2005/04/20 11:32
S10	130	S6 AND S7 AND S8 AND S9	USPAT	OR	ON	2004/09/26 11:37
S11	90	YAMAGUCHI-SATOSHI YAMAGUCHI-SATOSHI-INTELLECTUAL UETANI-YASUNORI MORIUMA-H MORIUMA-HIROSHI	USPAT	OR	ON	2005/04/20 11:30
S12	0	S10 AND S11	USPAT	OR	ON	2004/09/25 17:51
S13	1	S11 AND S4	USPAT	OR	ON	2004/09/25 17:51
S14	0	S11 AND S5 AND S8 AND S9	USPAT	OR	ON	2004/09/25 17:52
S15	14	S11 AND S5	USPAT	OR	ON	2004/09/25 18:02
S16	130	S10 NOT S15	USPAT	OR	ON	2004/09/25 18:02
S17	0	adamantylmethylbenzenesulfonate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 11:31
S18	0	adamantyl\$ylbenzenesulfonate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 11:31
S19	0	adamantyl\$yl adj benzene adj sulfonate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 11:31
S20	50413	ester adj group	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 11:36
S21	49240	toluenesulfonic adj acid	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 11:36
S22	19034	\$BENZENESULFONATE	USPAT	OR	ON	2004/09/26 11:37
S23	1966	(PHOTOACID ACID) ADJ GENERATOR	USPAT	OR	ON	2005/04/20 11:32
S24	251	S22 AND S23	USPAT	OR	ON	2004/09/26 11:37
S25	602594	POSITIVE	USPAT	OR	ON	2004/09/26 11:37
S26	3301	(PHOTOACID ACID) ADJ LABILE	USPAT	OR	ON	2004/09/26 11:37
S27	621337	RESIN RESIST PHOTORESIST	USPAT	OR	ON	2004/09/26 11:37
S28	130	S24 AND S25 AND S26 AND S27	USPAT	OR	ON	2004/09/26 11:37
S29	59008	\$25benzenesulfon\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 11:46

S30	2	jp-02025850-\$.did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 11:47
S31	2	jp-06123972-\$.did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 11:47
S32	2	jp-02150848-\$.did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 11:47
S33	2	jp-06043653-\$.did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 11:48
S34	8	S30 S31 S32 S33	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 11:50
S35	151	(S29 S21) and S26 and S27 and S20	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 11:51
S36	116	S35 not S28	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 11:51
S37	3	(US-6379860-\$ or US-6416928-\$).did. or (EP-794457-\$).did.	USPAT; DERWENT	OR	ON	2004/09/26 11:51
S38	116	S36 not S37	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 12:00
S39	4129	430/270.1.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 12:46
S40	18	S38 and S39	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 12:07
S41	2	"20040152009"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 12:08
S42	10162	sulfonate and (resist photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 12:30
S43	0	("2004/0152009").URPN.	USPAT	OR	ON	2004/09/26 12:09
S44	0	("2004/0152009").URPN.	USPAT	OR	ON	2004/09/26 12:09
S45	885	S23 and S42	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 12:30
S46	616	S45 and S39	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 12:30

S47	543	S25 and S46	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 12:31
S48	207	S20 and S47	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/09/26 12:31
S49	165	S48 not (S40 S41 S34 S28)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S50	1023	430/270.1.ccls.	US-PGPUB	OR	ON	2005/04/20 11:32
S51	493	S50 and S42	US-PGPUB	OR	ON	2004/09/26 12:47
S52	0	("2004/0018445").URPN.	USPAT	OR	ON	2004/09/26 15:13
S53	0	\$15ADAMANTYL\$8YLOXYCARBONYLBENZENESULFONATE	USPAT	OR	ON	2004/09/26 15:14
S54	0	\$15ADAMANTYL\$8YLOXYCARBONYL ADJ BENZENESULFONATE	USPAT	OR	ON	2004/09/26 15:14
S55	0	\$15ADAMANTYL\$8YLOXYCARBONYL ADJ BENZENE ADJ SULFONATE	USPAT	OR	ON	2004/09/26 15:15
S56	0	\$50YLOXYCARBONYL ADJ BENZENE ADJ SULFONATE	USPAT	OR	ON	2004/09/26 15:15
S57	5	\$50YLOXYCARBONYLBENZENESULFONATE	USPAT	OR	ON	2005/04/20 11:43
S58	0	\$50YLOXYCARBONYL ADJ BENZENESULFONATE	USPAT	OR	ON	2004/09/26 15:15
S59	2	("20040068573").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/26 15:42
S60	2	("20030068573").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/26 15:42
S61	0	("2004/0152009").URPN.	USPAT	OR	ON	2005/04/20 11:30
S62	478	YAMAGUCHI-SATOSHI YAMAGUCHI-SATOSHI-INTELLECTUAL UETANI-YASUNORI MORIUMA-H MORIUMA-HIROSHI	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:30
S63	6185	(PHOTOACID ACID) ADJ GENERATOR	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:31
S64	29511	\$BENZENESULFONATE	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/04/20 14:12
S65	2565193	RESIN RESIST PHOTORESIST	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:32
S66	7011	(PHOTOACID ACID) ADJ LABILE	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:32
S67	4788	430/270.1.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:32

S68	53418	ester adj group	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S69	51884	toluenesulfonic adj acid	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S70	19657	\$BENZENESULFONATE	USPAT	OR	ON	2005/04/20 13:03
S71	2179	(PHOTOACID ACID) ADJ GENERATOR	USPAT	OR	ON	2005/04/20 11:33
S72	303	S70 AND S71	USPAT	OR	ON	2005/04/20 11:33
S73	620311	POSITIVE	USPAT	OR	ON	2005/04/20 11:33
S74	3476	(PHOTOACID ACID) ADJ LABILE	USPAT	OR	ON	2005/04/20 11:33
S75	641168	RESIN RESIST PHOTORESIST	USPAT	OR	ON	2005/04/20 11:33
S76	155	S72 AND S73 AND S74 AND S75	USPAT	OR	ON	2005/04/20 11:33
S77	63532	\$25benzenesulfon\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 13:04
S78	2	jp-02025850-\$.did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S79	2	jp-06123972-\$.did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S80	2	jp-02150848-\$.did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S81	2	jp-06043653-\$.did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S82	8	S78 S79 S80 S81	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S83	174	(S77 S69) and S74 and S75 and S68	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S84	127	S83 not S76	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S85	3	(US-6379860-\$ or US-6416928-\$).did. or (EP-794457-\$).did.	USPAT; DERWENT	OR	ON	2005/04/20 11:33
S86	127	S84 not S85	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S87	4556	430/270.1.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S88	20	S86 and S87	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:50

S89	2	"20040152009"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S90	11159	sulfonate and (resist photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 14:13
S91	999	S71 and S90	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S92	704	S91 and S87	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S93	618	S73 and S92	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S94	245	S68 and S93	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:33
S95	191	S94 not (S88 S89 S82 S76)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 12:27
S96	5	S62 and S63 and S64 and S65 and S66	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:35
S97	11	S62 AND S63 AND S64 AND S65	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 11:45
S98	5	\$50YLOXYCARBONYLBENZENESULFONATE	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/04/20 13:04
S99	63532	\$25benzenesulfon\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 13:04
S10 0	19	\$50CARBONYLBENZENESULFONATE	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/04/20 13:05
S10 1	2	("20040018445").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/04/20 13:05
S10 2	0	("2004/0018445").URPN.	USPAT	OR	ON	2005/04/20 13:05
S10 3	2179	S71 same S63	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/04/20 14:20

S10 4	1857	S103 and (resist photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 14:20
S10 5	663	S104 and S66	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 14:16
S10 6	130903	cyclohexyl 2-norbornyl 1-adamantyl 2-adamantyl	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 14:16
S10 7	312	S105 and S106	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 14:20
S10 8	114	S70 same S63	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/04/20 14:20
S10 9	112	S108 and (resist photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 14:20
S11 0	95	S109 and S106	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/20 14:20